

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re U.S. Patent Application of)
FUKUDA et al.)
Application Number: To Be Assigned)
Filed: Concurrently Herewith)
For: MANUFACTURING METHOD FOR ELECTRONIC)
DEVICE)
ATTORNEY DOCKET NO. NITT.0250)

Honorable Assistant Commissioner
for Patents
Washington, D.C. 20231

INFORMATION DISCLOSURE STATEMENT

Pursuant to 37 C.F.R. §§ 1.56 and 1.97, this Information Disclosure Statement is submitted in the above-identified National Stage U.S. patent application. A listing of documents to be published on the face of any patent granted from this application is submitted herewith on Form PTO-1449. Any other documents or information submitted for consideration by the Examiner are listed in this paper. A copy of each U.S. and foreign patent, or each publication or portion thereof listed or herein identified, is submitted herewith.

CERTIFICATION

This Information Disclosure Statement is submitted with the initial filing of the application. Accordingly, no fee is due or payable at this time.

The Examiner is requested to acknowledge consideration of the information provided in this paper in accordance with prescribed procedures.

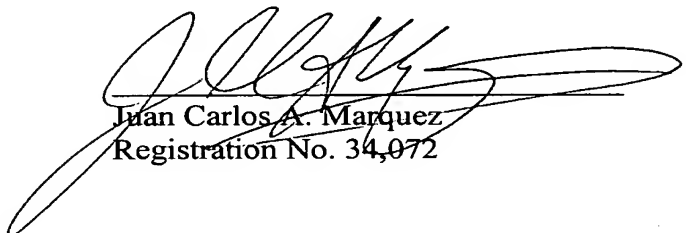
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	APPLICANT FUKUDA et al.	
	FILING DATE Concurrently Herewith	GROUP

U.S. Patent Documents

Examiner Initial	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE

Foreign Patent Documents

Examiner Initial	DOCUMENT NUMBER	FILING DATE	COUNTRY	CLASS	SUB- CLASS	TRANSLATION	
						YES	NO

Other Documents (Including Author, Title, Date Pertinent Pages, Etc.)

		Yukinori Ochiai et al., "High-Resolution, High-Purity Calix[n]arene Electron Beam Resist", Journal of Photopolymer Science and Technology, Vol. 13, No. 3 (2000), pp. 413-417
		Tetsuya Tada et al., "Improved Sensitivity of Multi-Adduct Derivatives of Fullerene", Journal of Photopolymer Science and Technology, Vol. 14, No. 4 (2001), pp. 543-546
		Tsuyohiko Fujigaya et al., "A New Photoresist Based on Poly(propyleneimine) Dendrimer", Journal of Photopolymer Science and Technology, Vol. 13, No. 2 (2000), pp. 339-344
EXAMINER		DATE CONSIDERED

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